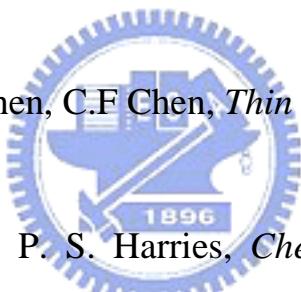


參考文獻

- [1] H. W. Kroto, J. R. Heath, S.C.O'Brien, R.F.Curl, R.E. Smalley, *Nature* 1985, 318, 162。
- [2] S. Iijima, *Nature* 1991, 354, 56。
- [3] Tobias Hertel, Robert E. Walkup, and Phaedon Avouris, *Physical Review B* 1998, Vol 58, Number 20.
- [4] Young-Gui Yoon, Mario S. C. Mazzoni, Hyoung Joon Choi, Jisoon Ihm, and Steven G. Louie, *Physical Review Letters* 2001, Vol 86, Number 4, 22 January.
- [5] Tobias Hertel, Richard Martel, and Phaedon Avouris, *J. Phys. Chem. B* 1998, 102, 910-915.
- [6] Changchun Zhu, Chunyu Wu and Weihua Liu, *IEEE* 2000, 537-539
- [7] Hui Lin Chang, Chao Hsun Lin, Cheng Tzu Kuo, *Diamond and Related Materials* 2002, 11 793-798.
- [8] A. Hirsch, *Angew. Chem. Int. Ed.* 2002, 41, 1853.
- [9] MS Dresselhaus, G Dresselhaus, R Satio, *Carbon* 1995, 33, 883-891.
- [10] W. A. de Heer, *Science* 1995, 270, 1179.
- [11] Y.I. Prylutskyy et al., *Computational Materials Science* 2000, 17, 352-355.
- [12] Valentin N. Popov, *Materials Science and Engineering: R: Reports* 2004, Volume 43, Issue 3, pp. 61-102
- [13] T. W. Ebbesen, H. J. Lezec, H. Hiura, J. W. Bennett, H. F. Ghaemi, T. Thio, *Nature* 1996, 382, 54.
- [14] J. Hone et al., *Synthetic Metals* 1999, 103, 2498.
- [15] A. Thess, P. Nikolaev, H. Dai, C. Xu, A. G. Rinzler, D. T. Colbert,

- G. E. Scuseria, R. E. Smalley, *Science* 1996, 273, 5274, 483-487.
- [16] T. Guo, P. Nikolaev, A. Thess, D. T. Colbert, R. E. Smalley, *Chem. Phys. Lett.* 1995, 243, 49.
- [17] Philip G. Collins, Keith Bradley, Masa Ishigami, A. Zettl, *Science* 2000, Vol 287.
- [18] J.H. Yen, I.C. Leu, C.C. Lin, M.H. Hon, *Diamond and Related Materials* 2004, 13, 1237–1241.
- [19] S.G. Wang, Q. Zhang, S.F. Yoon, J. Ahn, *Scripta Materialia* 2003, 48, 4, 409-412.
- [20] R.M. Liu, J.M. Ting, *Materials Chemistry and Physics* 2003, 82, 3, 571-574.
- [21] M. Chen, C.M. Chen, C.F. Chen, *Thin Solid Films* 2002, 420, 230-234.
- 
- [22] R. T. K. Baker, P. S. Harries, *Chem. Phys. Carbon* 1978, Marcel Dekker, New York, 83.
- [23] Y. Saito, T. Yoshikawa, M. Inagaki, M. Tomita, T. Hayashi, *Chem. Phys. Lett.* 1999, 304, 277.
- [24] A. Oberlin, M. Endo, T. Koyama, *Carbon* 1976, 14, 133.
- [25] A. Oberlin, M. Endo, T. Koyama, *J. Cryst. Growth* 1976, 32, 335.
- [26] T. Baird, J. R. Fryer, B. Giant, *Carbon* 1974, 12, 591.
- [27] R. T. K. Baker, J. J. Chludzinski, *Journal of Catalysis* 1980, 64, 464.
- [28] International Technology Roadmap for Semiconductors :
<http://public.itrs.net/>
- [29] S.J. Tans, A.R.M. Verschueren, C. Dekker, *Nature* 1998, 393, 29.
- [30] A. Javey, H. Kim, M. Brink, Q. Wang, A. Ural, J. Guo, et al., *Nature*

Mater 2002, 1, 241.

- [31] B.Q. Wei, R. Vajtai, P.M. Ajayan, *Appl. Phys. Lett.* 2001, 79, 1172.
- [32] A.P. Graham, G.S. Duesberg, R. Seidel, M. Liebau, et al., *Diamond & Related Materials* 2004, 13, 1296.
- [33] F. Kreupl, A.P. Graham, G.S. Duesberg, et al., *Microelectronic Engineering* 2002, 64, 399-408.
- [34] J. Li, Q. Ye, A. Cassell, et al., *Appl. Phys. Lett.* 2003, 82, 15.
- [35] A. Naeemi, R. Sarvari, J.D. Meindl, *IEEE Electron Device Letters* 2005, 26, 2.
- [36] A. Naeemi, J.D. Meindl, *IEEE Electron Device Letters* 2005, 26, 8.
- [37] S.M. Rossnagel, T.S. Kaun, *J. Vac. Sci. Technol. B, Microelectron. Process. Phenom.* 2004, vol. 22, no.1, 240-247.
- [38] Brian Chapman, *Glow Discharge Processes*, John Wiley and Sons 1980.
- [39] E. Nasser, *Fundamental of Gaseous Ionization and Plasma Electronics*, Wiley Interscience 1971.
- [40] 莊達人, *VLSI製造技術*, 高立圖書有限公司 1995.
- [41] P.X. Hou, S. Bai, Q.H. Yang, C. Lin, H.M Chang, *Carbon* 2002, 40, 81-5.
- [42] T. Saito, K. Matsushige, K. Tanake, *Physica B* 2002, 323, 280-3.
- [43] J.S. Kim, K.S. Ahn, C.O. Kim, J.P Hong, *Appl. Phys. Lett.* 2003, 82, 1690-2.
- [44] Q.H. Wang, T.D. Corrigan, J.Y. Dai, R.P.H. Chang, A.R. Krauss, *Appl. Phys. Lett.* 1997, 70, 3308.
- [45] C.Y. Zai, X.D. Bai, E.G. Wang, *Appl. Phys. Lett.* 2002, 81, 1690.

- [46] H. Burbert, S. Haiber, W. Brandl, G. Marginean, M. Heintze, V. Bruser, *Diamond Relat. Mater* 2003, 12, 811.
- [47] K.S. Ahn, J.S. Kim, C.O.Kim, J.P Hong, *Carbon* 2003, 41, 2481-5.
- [48] Y. Liu, L. Liu, P. Liu, L. Sheng, S. Fan, *Diamond & Related Materials* 2004, 13, 1609-13.
- [49] A. Patil, R. Vaia, L. Dai, *Synthetic Metals* 2005, 154, 229-232.
- [50] G. Smolinsky and D. L. Flamm, *J. Appl. Phys.* 1979, Vol. 50, p. 4982-4987.
- [51] http://www.usc.edu/dept/CEMMA/vj_xps.html
- [52] 莊東榮 掃描式光電子能譜顯微儀 科學月刊 第29卷第一期 P.22.
- [53]http://niufood.niu.edu.tw/img.php?img=662_51121f09.png&dir=users_sharing/1
- [54] <http://www.me.sophia.ac.jp/~takai/TDS.htm>
- [55] 楊金成、柯富祥、孫旭昌、戴寶通 奈米通訊 第六卷第二期
TD-APIMS晶圓表面分析系統介紹
http://www.ndl.org.tw/cht/ndlcomm/P6_2/43.htm
- [56]<http://tech.digitimes.com.tw>ShowNews.aspx?zCatId=345&zNotesDocId=05D60F44E6DAC9B648257038003DD9D0>
- [57] <http://elearning.stut.edu.tw/caster/3/no6/6-2.htm>
- [58] http://www.ndl.org.tw/ndl2006/department/nmlab/device_cafm.html
- [59] http://www.spm.com.cn/afm_mode.shtml
- [60] <http://elearning.stut.edu.tw/caster/3/no3/3-3.htm>